

L Number	Hits	Search Text	DB	Time stamp
1	89	((photosensitive near2 (paste film) photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate)) and glycidyl and ethylenically adj (unsaturated double) adj bond)	USPAT; US-PGPUB	2003/12/23 16:49
2	27	((photosensitive near2 (paste film) photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate)) and glycidyl and ethylenically adj (unsaturated double) adj bond) and ethylenically adj unsaturated adj bond same no	USPAT; US-PGPUB	2003/12/23 16:41
3	42	((photosensitive near2 (paste film) photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate)) and glycidyl and ethylenically adj (unsaturated double) adj bond) and acid adj anhydride	USPAT; US-PGPUB	2003/12/23 16:42
4	30	((Photosensitive near2 (paste film) photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate)) and glycidyl and ethylenically adj (unsaturated double) adj bond) and acid adj (number value) and (molecular adj weight dalton)	USPAT; US-PGPUB	2003/12/23 16:43
5	42	((((photosensitive near2 (paste film) photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate)) and glycidyl and ethylenically adj (unsaturated double) adj bond) and acid adj anhydride) and (stabil\$2er acid phosphor\$4 sulf\$6)	USPAT; US-PGPUB	2003/12/23 16:44
6	3	((photosensitive near2 (paste film) photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate)) and glycidyl and ethylenically adj (unsaturated double) adj bond) and (low adj melting silicate zinc bismuth lithium) near2 glass near2 (powder particle) and (metal oxide) near2 (powder particle granule) and (particle grain) near2 (size diameter micron) and (wt weight) near2 (percent '%' part)	USPAT; US-PGPUB	2003/12/23 16:47
7	10	((photosensitive near2 (paste film) photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate)) and glycidyl and ethylenically adj (unsaturated double) adj bond) and ((low adj melting silicate zinc bismuth lithium) near2 glass near2 (powder particle) (metal oxide) near2 (powder particle granule) and (particle grain) near2 (size diameter micron) and (wt weight) near2 (percent '%' part)	USPAT; US-PGPUB	2003/12/23 16:48
9	18	((photosensitive near2 paste photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate))) and ((glass metal oxide) near2 (particle powder) acid adj (value number) (molecular adj weight dalton) (particle grain) near2 (size diameter) (wt weight) near2 (part percent '%'))	EPO; JPO; DERWENT	2003/12/23 16:50
10	7	((photosensitive near2 paste photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate))) and glycidyl	EPO; JPO; DERWENT	2003/12/23 16:50
11	4	((photosensitive near2 paste photoresist photocurable) and (polymer copolymer) and ((acrylic methacrylic vinylacetic) adj acid and (styrene methylstyrene metha\$2acrylate))) and acid adj anhydride	EPO; JPO; DERWENT	2003/12/23 16:50
12	41	ichikawa near2 kyo.in. takagi near2 kouichi.in. nobuyuki near2 suzuki.in	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/23 16:51

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13	30	10087769.did. 09316149.did 09218509.did. 11031416.did. 10273338.did 07248619.did. 1048815.did. 1087769.did. 9316149.did 9218509.did 1131416.did. 10273338.did. 7248619.did "5973034"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/23 16:52
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